



Figure 1. a) Grown Pd film thickness on sputtered Pd by alternating Pd(hfac)₂ and different plasma combinations at 100°C as a function of numbers of cycles. The full lines are the linear least-square fits to the data sets. b) Growth per cycle (GPC) of Pd ALD using different plasma combinations at 100°C, 150°C and 200°C (200 cycles are performed for each process)